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Beyond Ni/Au: Next Generation Corrosion-Resistant Finishes for Electronics Applications

SUR/FIN 2018 - Cleveland, OH

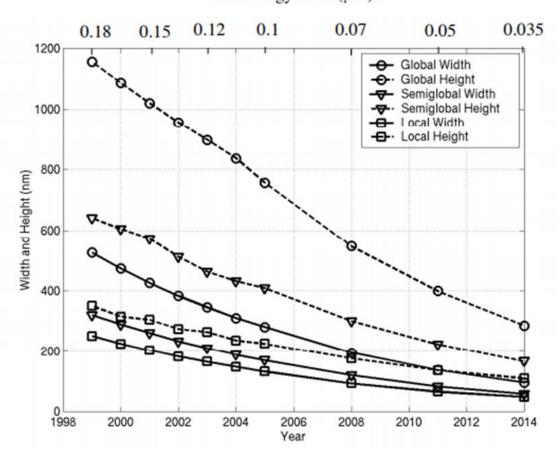
Beyond Ni/Au: Functions of Electronic Finishes

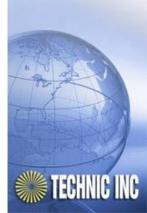
- Provide electrical conductivity
- Improve corrosion resistance
- Impart good wear resistance
- Enable attachment to other surfaces (where applicable)
 - Soldering, insertion, etc.
- Traditional electroplated Ni/Au deposits have achieved the above objectives successfully for decades
 - Ni: 1-2 μm +
 - Au: 0.1-0.75 μm (depending on application)
- UNTIL NOW...



Beyond Ni/Au: Electronic Finishes : New Requirements

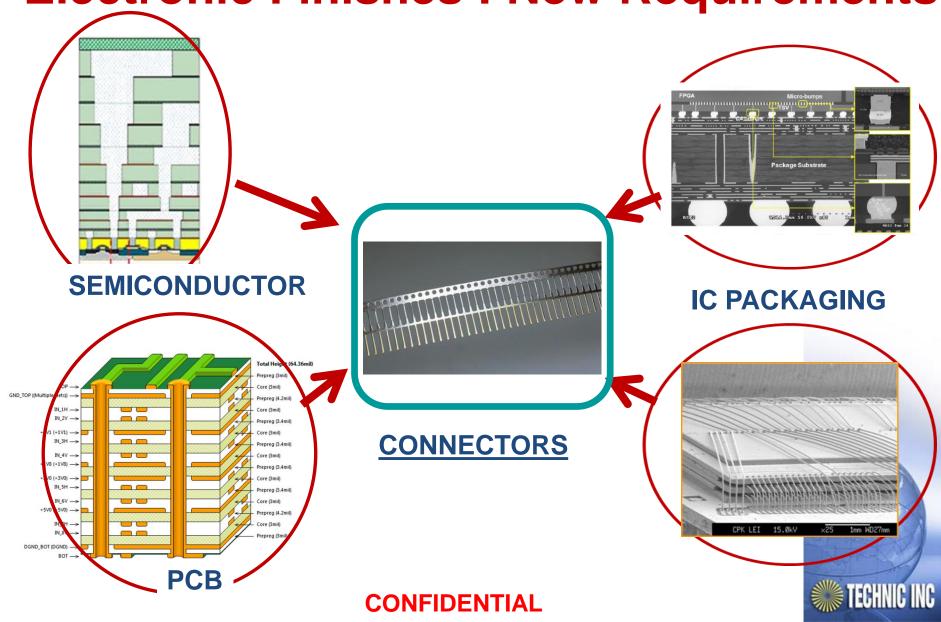
As IC semiconductor devices and PCB dimensions are scaled down, the demands on the electronic interconnects increase dramatically Technology node (µm)



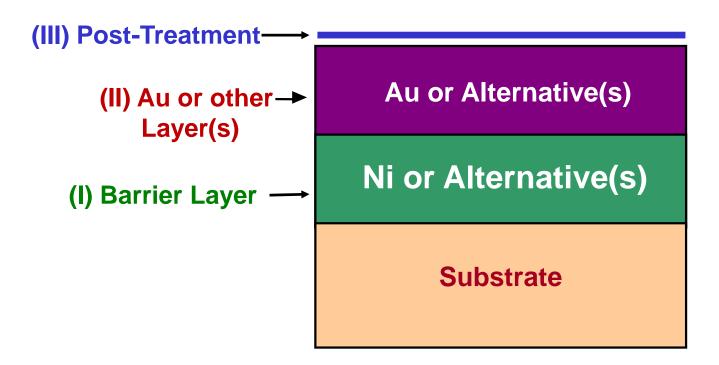


Beyond Ni/Au:

Electronic Finishes: New Requirements



Beyond Ni/Au: Typical Electronic Finish





Improved Barrier Layers



Nano-Crystalline Nickel

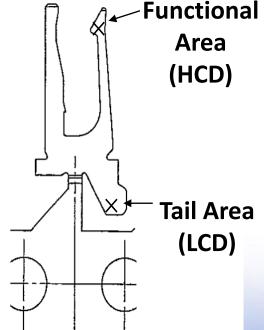
- Traditional barrier layer for electronics finishes is matte nickel sulfamate
- Nano-crystalline Nickel is an advanced nickel electroplating process specifically engineered to significantly improve nickel thickness distribution and corrosion-resistance from a proprietary electrolyte in high speed/reel-to-reel plating applications
- Nano-crystalline Nickel produces a semi-bright, low stress, ductile deposit

Nano-Crystalline Nickel vs. Ni sulfamate

Deposit Characteristics				
	Nano-crystalline Ni	Ni Sulfamate Matte		
Appearance	Semibright	Matte		
Stress	~2500 psi (17.2 MPA)	~5500 psi (37.0 MPA)		
Hardness	~450 knoop	~250 knoop		
Structure	Nano-crystalline	Micro-crystalline		
Solution Conductivity	155.6 mS/cm	68.0 mS/cm		

Nano-crystalline Ni vs. Ni Sulfamate Thickness Distribution Comparison

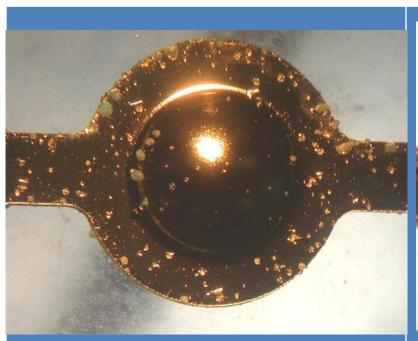
Bath	HCD (u")	LCD (u")	HCD:LCD Ratio
Ni S.	41	14	2.9
GE Ni	43	22	2.0
Ni S.	84	32	2.6
GE Ni	86	49	1.8
Ni S.	123	47	2.6
GE Ni	121	72	1.7



The thickness distribution of the Low Current Density (LCD) area is significantly improved (30 to 40%) by Nano-Ni process.



Nano-Crystalline Nickel vs. Ni sulfamate Corrosion Comparison





Ni sulfamate – 120μin Au - 30μin Nano-Ni - 100μin Au - 30μin

After 2 hour nitric acid vapor (NAV) exposure

Cobalt-Tungsten (CoW) A Nickel-Free Barrier Layer

- For certain applications, elimination of nickel entirely from the plated layer system is desirable (e.g., Ni dermatitis)
- Cobalt-Tungsten alloy (CoW) barrier layer electroplating technology has been developed for these applications

CoW Properties

Alloy composition: 65/35 ± 5% Co/W.

Hardness: 600-700 HV

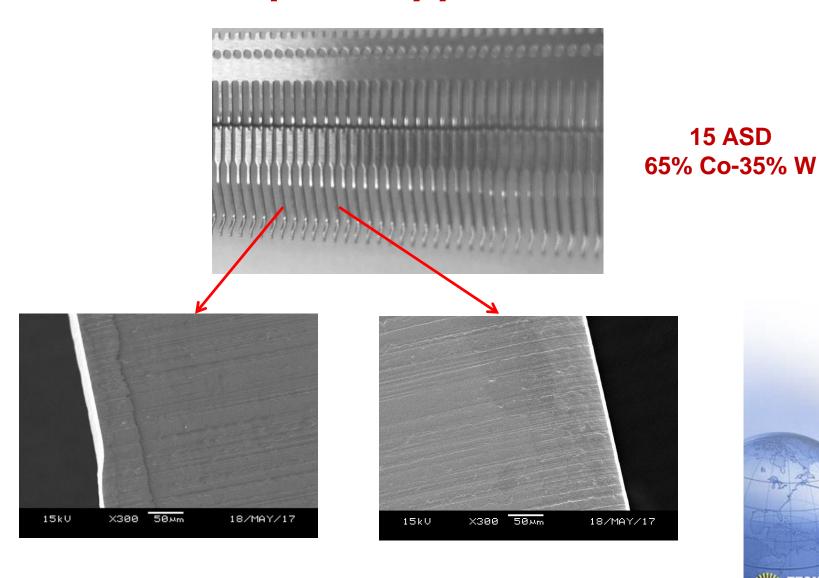
Deposit structure: Nano-crystalline

Wide operating window.

- Drop-in replacement for nickel or nickeltungsten plating solutions in existing lines.
- Nickel-free deposit with no nickel dermatitis issues - suitable for consumer applications
- Low deposit stress
- Excellent corrosion-resistance



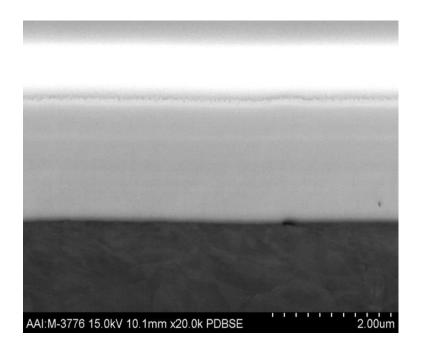
Cobalt-Tungsten Alloy Deposit Appearance

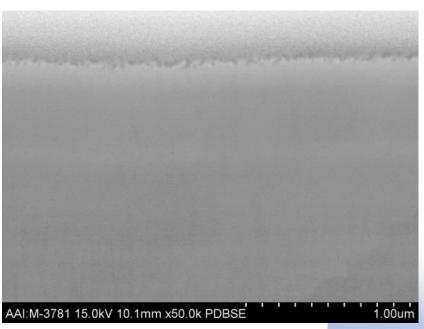




Cobalt-Tungsten Alloy FIB / SEM Cross-section data

20,000X 50,000X

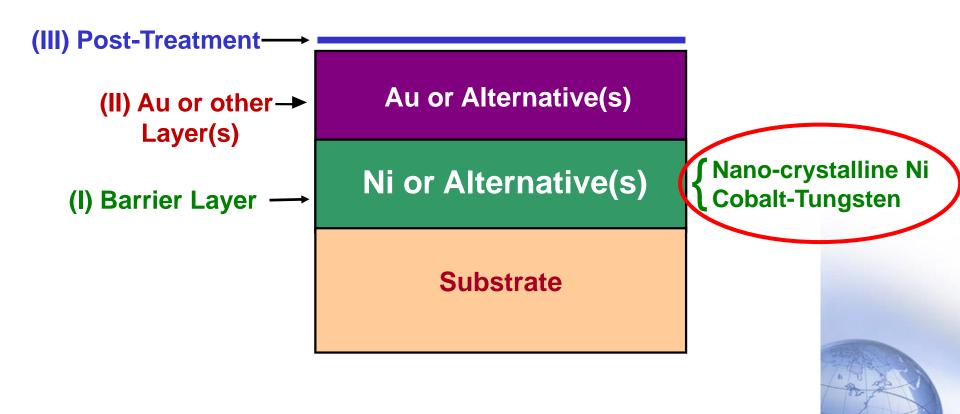




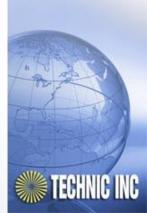
CoW has nano-crystalline structure



Beyond Ni/Au: Typical Electronic Finish

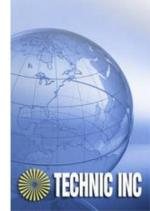


Alternatives to Gold / Post-Treatment Processes

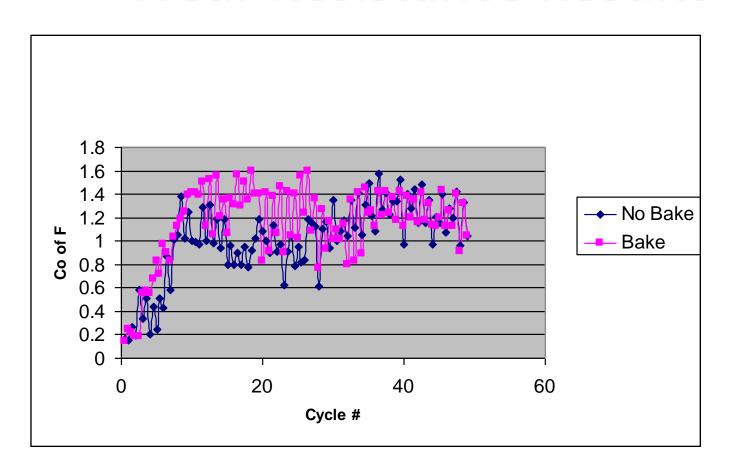


Silver on Connectors-Introduction

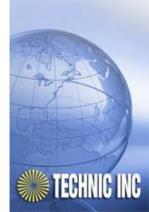
- Until today, 2 technical issues have limited silver's implementation in non-automotive applications
 - Wear resistance esp. after multiple insertion cycles
 - Corrosion resistance overcoming the silver tarnish issue
 - Automotive use of silver is currently restricted to sealed applications with minimal insertions
- Solution: Wear-resistant /corrosionresistant silver plating process



Conventional Silver Wear Resistance Results

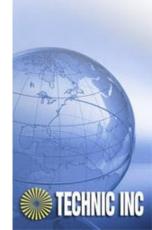


CoF of conventional silver is high ~1.2 before & after bake



Silver Alloy Plating

- Silver alloy plating from a two-part system consisting of a silver alloy electroplated deposit and a unique post-treatment process chemistry.
- This combination provides excellent deposit conductivity combined with superior corrosion properties and significantly improved wear resistance compared to conventional silver.

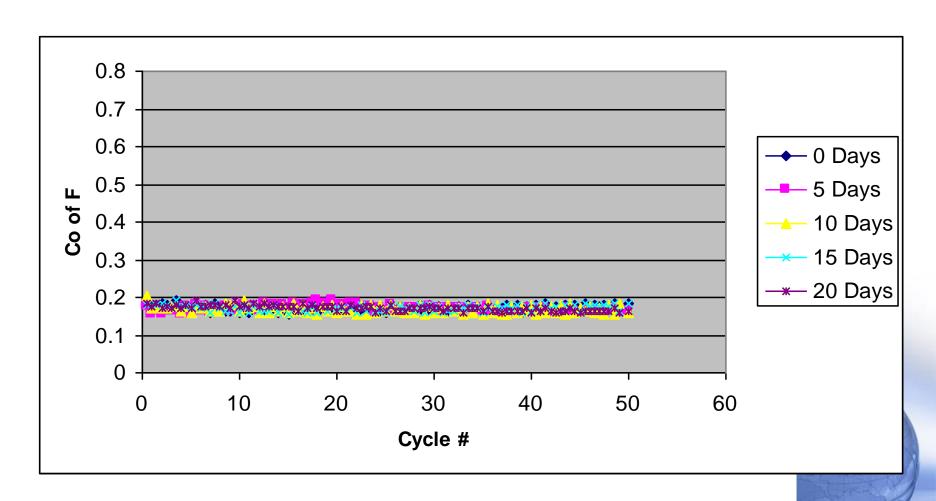


Silver Alloy Plating Summary

- Deposit Hardness
 - 175 Knoop as-plated; 145 Knoop after bake
- Contact Resistance √
 - Low and stable CR (~2.5m-ohm), after bake and/or after
 20 days exposure to MFG
- Wear Resistance $oldsymbol{\mathsf{V}}$
 - Low and stable CoF (~0.2), after bake and/or after 20 days exposure to MFG
- Corrosion Resistance $\sqrt{}$
 - Minimal to no corrosion after 20 days exposure to MFG
- Solderability ${f V}$
 - Passes J-STD-002C after 500 hrs bake



DurasilTM Wear Resistance Results With bake / 0-20 days MFG Exposure





DurasilTM Corrosion Resistance Results 0-20 days MFG Exposure



Above: no bake Below: with bake

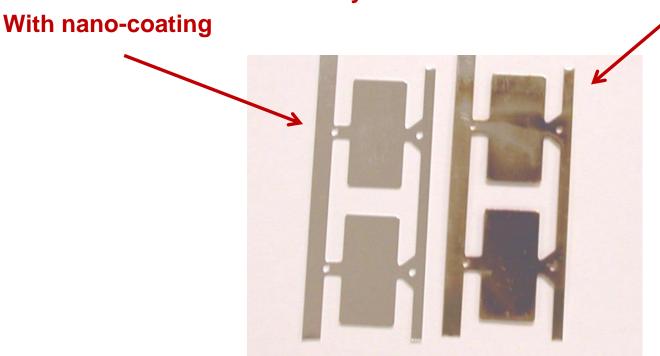


TECHNIC INC

Conclusion: Minimal to no corrosion observed after 20 days MFG exposure

Inorganic Nano-Coating on Silver Sulfur Corrosion Testing

5% K2S Solution
Parts fully immersed for 5 minutes



No Treatment

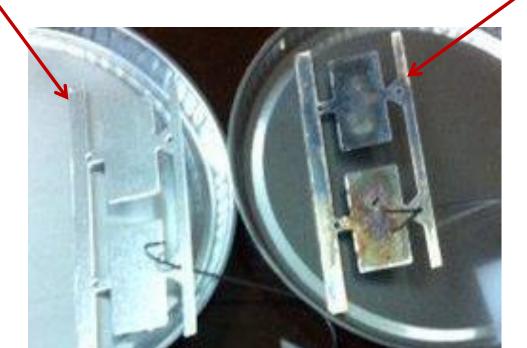




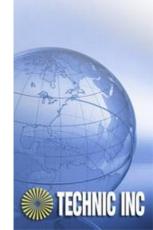
Inorganic Nano-Coating on Silver Sulfur Corrosion Testing

Mixed Flowing Gas Exposure per EIA-364-65B, Class IIa 5 days exposure

With nano-coating



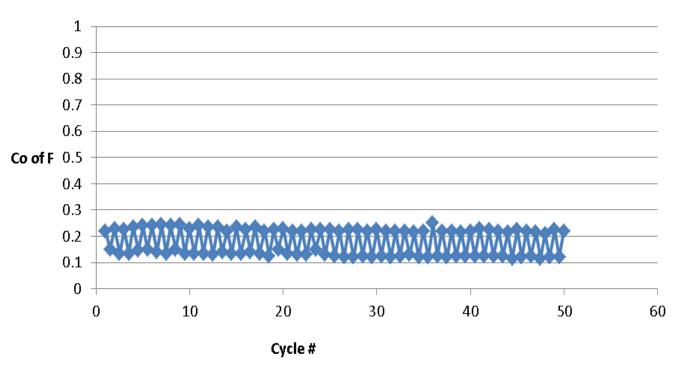




No Post-Treatment

Nano-coating + lube

Wear Resistance Results



Excellent WR results equivalent to hard gold



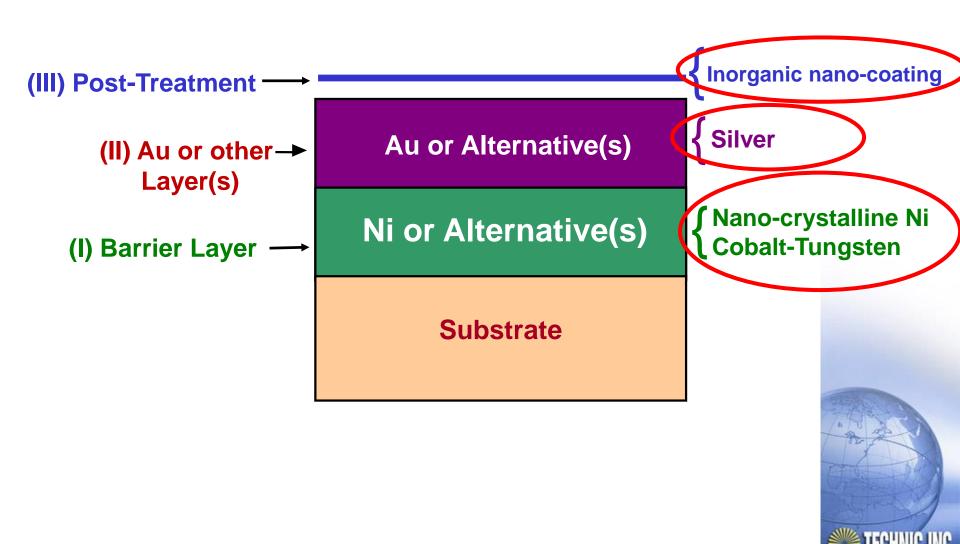


Silver on Connectors Summary

- Several options exist :
 - Silver alloy plating + post-treatment
 - Silver plating with nano-coating for corrosion protection only
 - Silver plating with 2-step post-treatment process sequence consisting of nano-coating + Post-Dip (lube), improvements in both silver protection AND wear resistance can be achieved
- These combinations provide similar technical performance comparable to hard gold in connector and related applications



Beyond Ni/Au: Typical Electronic Finish



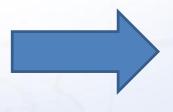
Emerging Applications Requiring Completely New Electronic Finishes:

- Electrolytic Sweat Resistant (ESR)
 Connector Finishes
 - Press-Fit Connector Pins
 - High Frequency Applications (5G)

Mobile Phone Connector Plating Technology Shift

- Two recent changes in cell phone technology are having a major impact on the plated finishes used for mobile phone connectors:
 - I. Replacement of traditional headphone jack with a single connector that performs both the electrical charging function and the headphone connection

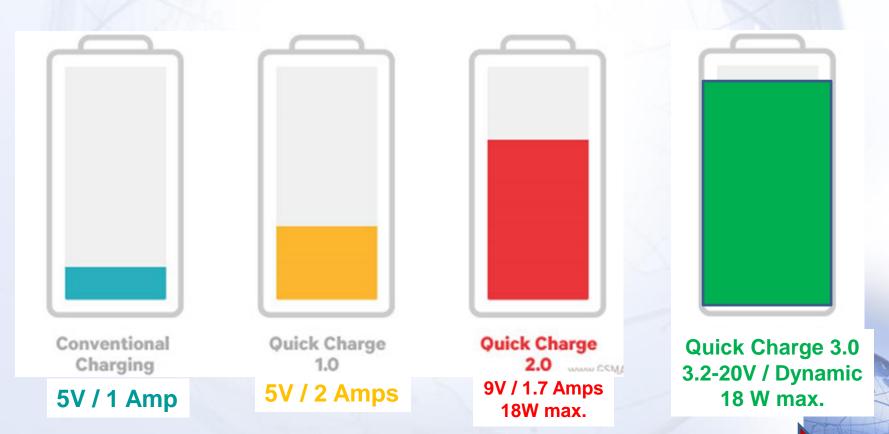






Mobile Phone Connector Plating Technology Shift

II. Implementation of 'quick-charge' connector technology



How does this affect Mobile Phone Connector Plating Technology?

I. Consumers exercising while using head phones &/or charging their cell phones (i.e., handling the connector) results in human sweat being present on the plated connector in the presence of electrical current

Sweat + Electrolysis = CORROSTON







II. This electrolytic sweat-induced corrosion issue is made more severe when combined with the higher charging current/volts of quick charge technology



USB-C Connector Pins









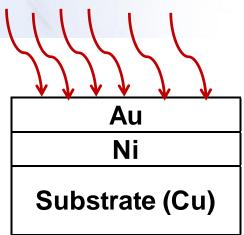


Mechanism of Corrosion Using Various Test Methods

NAV Test



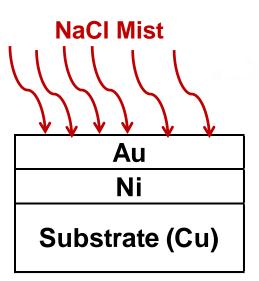
Nitric Acid Fumes



Mechanism =
Corrosion occurs
from outside to inside

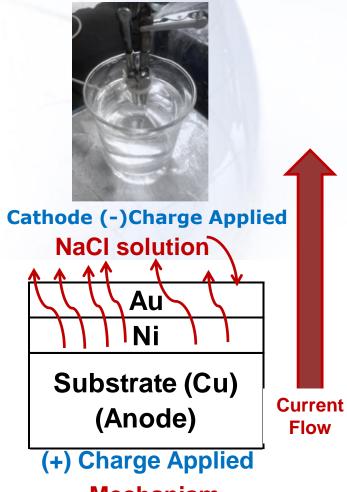
NSS Test





Mechanism =
Corrosion occurs
from outside to inside

Electrolytic Sweat Test



Mechanism =
Corrosion occurs
from INSIDE to OUTSIDE

Requirements for Passing ESR Testing

- Base material preparation is critical
- Extremely corrosion-resistant barrier layer(s) is (are) required
 - Ni cannot be used for high-end applications
- Top layer must be a <u>Rh-containing deposit</u> (resistant to electrolytic sweat solution)
 - No gold (gold is easily attacked/corroded during ESR testing)
- Optimal layer system to be selected depends on trade-off of performance vs. cost

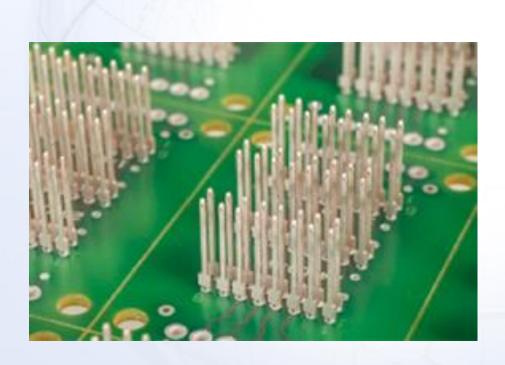


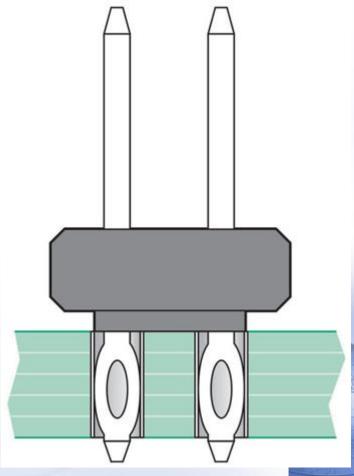
ESR Performance vs. Cost Summary

	ESR	
Classification	Performance	Cost
Low-End	3-4 minutes	1.5 X
Mid-End	4-20 minutes	2.4 - 7X
High End	20-40 minutes	7 - 10 X
Utra High End	40-70 minutes	10 - 12X



New Plating Technology for Connector Press-Fit Pin Applications





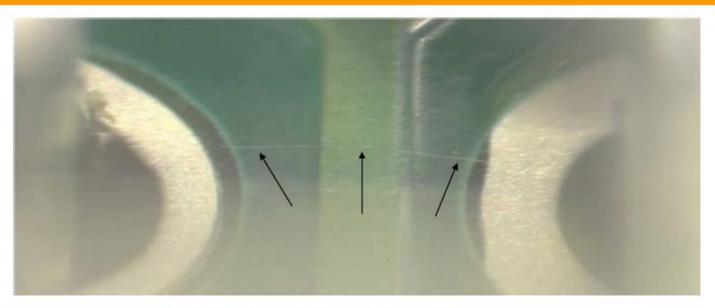
Connector Press-Fit Pin Plating Technology - Introduction

- Matte tin has resulted in extremely long whiskers under certain press-fit conditions
- Connector companies and/or end users have been experimenting with various nontin solutions for years
- Recently two alternative finishes have emerged as potential solutions for press-fit pin whiskers formed under compression

Matte Tin – Whiskers formed under compression

Occurrence of short circuits

Whiskers potentially create short circuits or parasitary current paths. Fast growth of whiskers can be observed in press-fit connections due to high mechanical stress at pure tin surfaces.



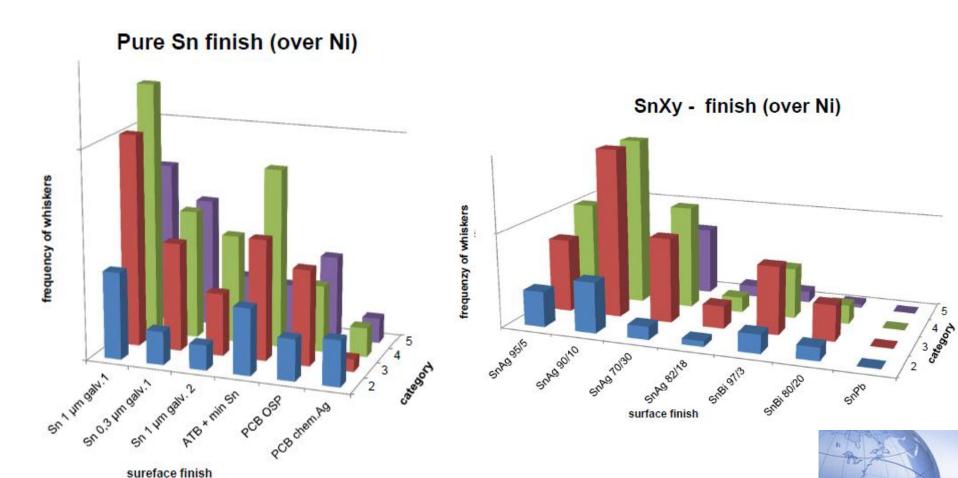
- Some 0-km and field returns identified at a body controller 2007
- Whiskers create direct parasitary signal path at sensor exits (very low current flow)
- Whisker length > 2 mm within 2-6 weeks after insertion in this case

Direct bridging of low signal electrical contacts

Source: "Whiskers and Alternative Surface Finishes at Press-in Technology" Dr. Hans-Peter Tranitz, Continental AG



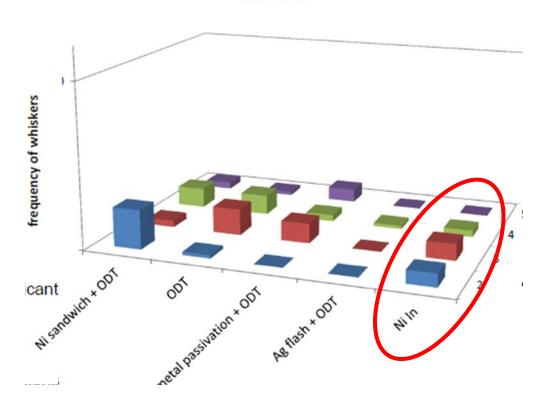
Tin Whisker Growth Comparison



Source: "Whiskers and Alternative Surface Finishes at Press-in Technology" Dr. Hans-Peter Tranitz, Continental AG

Tin Whisker Growth Comparison

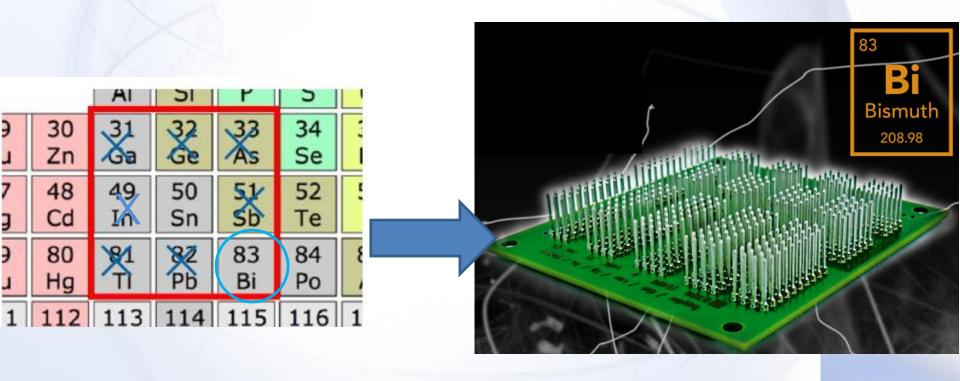
Sn - free



<u>Indium</u> is now a qualified/specified finish for some press-fit applications

Source: "Whiskers and Alternative Surface Finishes at Press-in Technology" Dr. Hans-Peter Tranitz, Continental AG

Press-Fit Pins Alternatives to Indium



Bismuth is also being considered as an option for certain press-fit applications

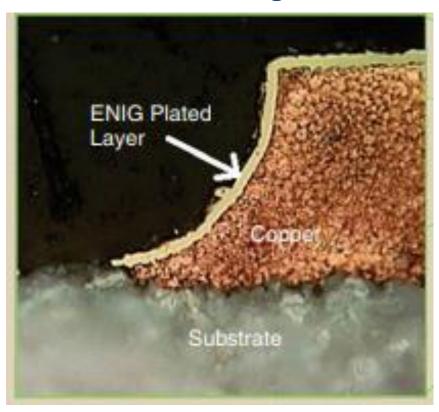
Source: "Litesurf –Tin-Free Electroplating for Press-Fit Technology," Frank Schabert TE Connectivity, Webinar presented March 2018

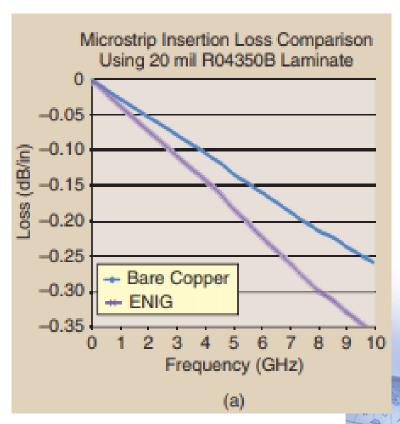
High Frequency Applications (5G)



Beyond Ni/Au: High Frequency Applications

Signal Loss vs. PCB Final Finish





Nickel deposit is the source of signal loss in high frequency applications

Source: "Ambiguous Influences Affecting Insertion Loss of Microwave Printed Circuit Boards" John Conrood, IEEE Microwave Magazine, Issue 1527-3342/12

Connector Finishes for High Frequency Applications (5G)

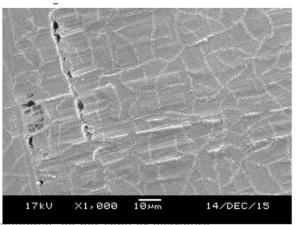
- Ni-free barrier layer is required
- Good conductivity and corrosion resistance for final finish
- Palladium (Pd) is a suitable deposit that can function as both a barrier layer and a final finish
 - Barrier layer effectiveness requires relatively high thickness (>0.75-1.0 μm)
 - HOWEVER electroplated Palladium is notorious for micro-cracking at high thickness
- Solution: micro-crack free Palladium



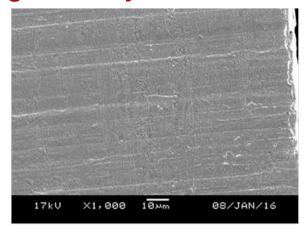
Low Stress/High Ductility Palladium

- Low stress deposits
 - No spontaneous microcracking up to 4 µm Pd thickness
 - No bending cracks (up to 2µm)
- Neutral pH / no ammonia smell
- Wide current density range
- Stable electrolyte
 - >5 MTO bath life, with periodic c-treatment

Conventional Pd-Cracked

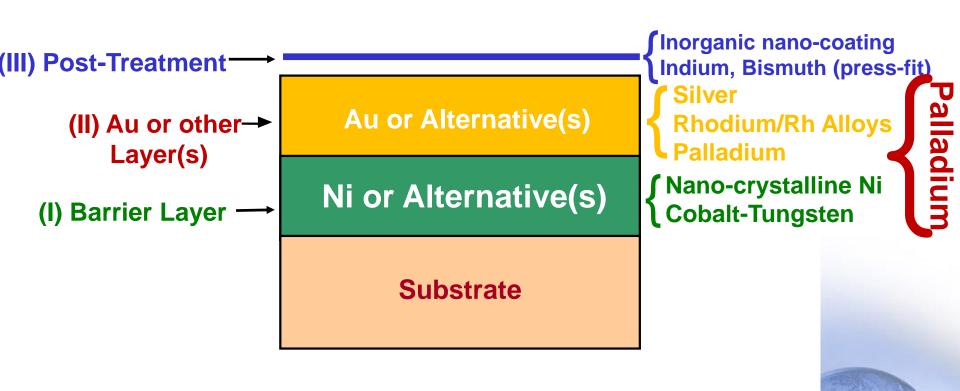


High Ductility Pd- No cracks





Beyond Ni/Au: Summary



Beyond Ni/Au: Conclusions

- Rapid changes are occurring in an industry where conventional Ni/Au has been used for 4 decades
- Alternative finishes are being considered and/or implemented, including exotic materials never before considered feasible in a connector application
- We expect additional changes will occur as connector finish technology needs to keep up with the demands of the other interconnects and/or use environments



Thank you!

